

	Ref #	Hits	Search Text	DBs
4	S4	26	(polariz\$4 same (expos\$4 or illuminat\$4 or beam) same pattern) and ((mask or reticle or photomask) same (contact\$3hole or hole) same (pitch or features))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB
6	S6	3	(polariz\$4 same (expos\$4 or illuminat\$4 or beam) same single same angle same (varies or varying or chang\$3 or optimiz\$4 or variable or differ\$3 or alter\$3)) and ((mask or reticle or photomask) same (contact\$3hole or hole) same (pitch or features))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
7	S7	55	(polariz\$4 same (expos\$4 or illuminat\$4 or beam) same single same angle same (varies or varying or chang\$3 or optimiz\$4 or variable or differ\$3 or alter\$3)) and ((mask or reticle or photomask) same (expos\$4 or irradiat\$4 or illuminat\$4) same (photoresist or resist or photosensitive))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
8	S8	21	(polariz\$4 same (expos\$4 or illuminat\$4 or beam) same single same angle same (varies or varying or chang\$3 or optimiz\$4 or variable or differ\$3 or alter\$3) same (imag\$4 or pattern\$4)) and ((mask or reticle or photomask) same (expos\$4 or irradiat\$4 or illuminat\$4) same (photoresist or resist or photosensitive))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB